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Erwin Kessels is a full professor at the Department of Applied Physics of the Eindhoven University of Technology TU/e (The Netherlands). He is also the scientific director of the NanoLab@TU/e facilities which provides clean room infrastructure for R&D in nanotechnology. Erwin received his M.Sc. and Ph.D. degree (with highest honors) in Applied Physics from the TU/e in 1996 and 2000, respectively. After obtaining international experience at the University of California Santa Barbara, Colorado State University and Philipps University in Marburg, he was appointed as assistant professor at the TU/e in 2002. He was promoted to full professor in 2011. His research interests cover the field of synthesis of ultrathin films and nanostructures using methods such as (plasma-enhanced) chemical vapor deposition (CVD), atomic layer deposition (ALD) and atomic layer etching (ALEt) for a wide variety of applications, mostly within the areas of nanoelectronics and photovoltaics. Within the field of ALD, he has contributed most prominently by his work on plasma-assisted ALD and his research related to ALD for photovoltaics. Erwin chaired the International Conference on Atomic Layer Deposition in 2008, has won several awards (including the Peter Mark Memorial Award from the American Vacuum Society) and he has published over 250 papers and holds 3 patents.